

****FACSIMILE COVER SHEET****

TO: Exr. J. Mercado
USPTO
Group 2825

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Re: Amendment Under 37 CFR §1.115

Your Ref: USSN 09/138,429

Our Ref: AM-2406

REMARKS


Attached is a preliminary amendment:
(1) Transmittal Letter (1 p., duplicate)
(2) Amendment Under 37 CFR §1.115 (6 pp.)

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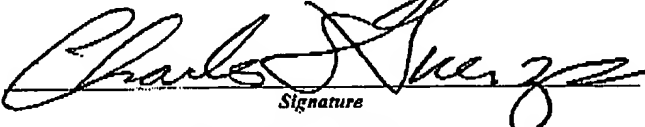
I certify that the above papers are being faxed to the above fax number
on January 23, 2003.

TECHNOLOGY CENTER 2800


Charles S. Guenzer
Reg. No. 30,640

Date: _____

No. of Pages (including cover): 9

AMENDMENT TRANSMITTAL LETTER (Large Entity)				Docket No. AM-2406	
Applicant(s): Imran HASHIM et al.					
Serial No. 09/138,429	Filing Date August 28, 1998	Examiner J. Mercado		Group Art Unit 2825	
Invention: COLLIMATED AND LONG THROW MAGNETRON SPUTTERING OF NICKEL/IRON FILMS FOR MAGNETIC RECORDING HEAD APPLICATIONS					
<u>TO THE ASSISTANT COMMISSIONER FOR PATENTS:</u>					
Transmitted herewith is an amendment in the above-identified application. The fee has been calculated and is transmitted as shown below.					
CLAIMS AS AMENDED					
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST # PREV. PAID FOR	NUMBER EXTRA CLAIMS PRESENT	RATE	ADDITIONAL FEE
TOTAL CLAIMS	24 -	20 =	4 x	\$18.00	\$72.00
INDEP. CLAIMS	3 -	3 =	0 x	\$84.00	\$0.00
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					\$0.00
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT					\$72.00
<input type="checkbox"/> No additional fee is required for amendment. <input checked="" type="checkbox"/> Please charge Deposit Account No. 50-0636 in the amount of \$72.00 A duplicate copy of this sheet is enclosed. <input type="checkbox"/> A check in the amount of to cover the filing fee is enclosed. <input checked="" type="checkbox"/> The Commissioner is hereby authorized to charge payment of the following fees associated with this communication or credit any overpayment to Deposit Account No. 50-0636 A duplicate copy of this sheet is enclosed. <input checked="" type="checkbox"/> Any additional filing fees required under 37 C.F.R. 1.16. <input checked="" type="checkbox"/> Any patent application processing fees under 37 CFR 1.17.					
FAX RECEIVED JAN 23 2003 TECHNOLOGY CENTER 2800					
 Signature			Dated: January 23, 2003		
Charles S. Guenzer, Reg. No. 30,640 (650) 566-8040 Mailing Address: Applied Materials, Inc. Patent/Legal Department P.O. Box 450A Santa Clara, CA 95052					
I certify that this document and fee is being deposited on with the U.S. Postal Service as first class mail under 37 C.F.R. 1.8 and is addressed to the Assistant Commissioner for Patents, Washington, D.C. 20231.					
Signature of Person Mailing Correspondence					
Typed or Printed Name of Person Mailing Correspondence					
CC:					

3600.2406
January 23, 2003 (1:44pm)

Docket: AM-2406

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Imran HASHIM et al

Attorneys Docket: AM-2406

Serial No.: 09/138,429

Art Unit No.: 2825

Filed: August 24, 1998

Examiner: J. Mercado

For: "COLLIMATED AND LONG THROW MAGNETRON SPUTTERING OF
NICKEL/IRON FILMS FOR MAGNETIC RECORDING HEAD APPLICATIONS"

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Commissioner of Patents
Washington, DC 20231

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PRELIMINARY AMENDMENT UNDER 37 CFR §1.115

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Sir:

In a preliminary amendment for consideration before initial examination of the Request for Continued Examination filed November 27, 2002, please amend the above application as follows:

Replace the claims with:

21. (Amended) An apparatus for depositing a magnetic film, comprising:
a sputtering chamber containing a target comprising a magnetic sputtering material, a substrate support having a substrate surface that is separated from the target, and a grounded collimator positioned between the target and the substrate support; and
an annular magnet array disposed within the sputtering chamber, the annular magnet array being configured to form a magnetic field that is substantially parallel to the substrate surface of the substrate support, the annular magnet array being concentrically positioned around an outer perimeter of the substrate surface of the substrate support.

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